Preliminary test beam results of SOI monolithic pixel detector

R. Dasgupta*

On behalf of the CLIC detector and physics (CLICdp) collaboration and Cracow groups: AGH-UST and IFJ-PAN

* AGH University of Science and Technology

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- SOI technology for monolithic pixel design
- System characterization
 - SOI prototype chip overview
 - Testbeam setup
- Measurement results
 - Correlation with telescope
 - Energy distribution
 - Clusterization methods
 - Position reconstruction
 - Alignment correction
 - Spatial resolution
- Summary

Monolithic pixel detectors in SOI

Properties

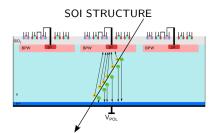
• Minimum pitch $< 10 \ \mu m$

SOI technology for monolithic pixel design

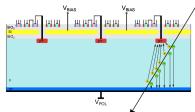
- Small sensor capacitance (good SNR)
- Double SOI → radiation hardness.
- Wide temperature range (4 400K)
- Thinner and cheaper then hybrid solutions

Double Silicon-On-Insulator

- voltage applied on Mid-Si layer allows to correct the potential changes caused by positive charges induced by irradiation,
- Mid-Si shields electronic from negative influence of high voltage needed for fully depletion.



DOUBLE SOI STRUCTURE



Lapis 200 nm Fully-Depleted Low-Leakage SOI CMOS with four wafer types: FZ(n), CZ(n), FZ(p) and Double SOI(p)

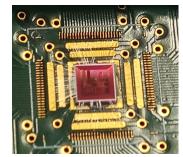
- submatrixes with different source-followers and charge pre-amplifiers, various layouts and transistor sizes.
- in total 16×36 pixels,
- $30\mu m \times 30\mu m$ pixel size $\rightarrow \sim 0.52 \ mm^2$ matrix area.
- rolling shutter readout (integration time for one frame: $150\mu s$),
- different wafer types (FZ(n),CZ(n), FZ(p) Double SOI) with different substrate thickness (300-500 μm) and resistivity $(2k\Omega, 700\Omega, 8k\Omega)$
- technology allows to fabricate thin wafer down to 50 μ m.

For this study only source-follower pixels were used on FZ(n) wafer.

Very small size of submatrixes (different gain, noise) worsens achievable position resolution.



| 4X6 | 4X6 |
|---------------------------|-----|
| 4X6 | 4X6 |
| 8X6 | |
| SOURCE-FOLLOWER PIXELS | |
| | |

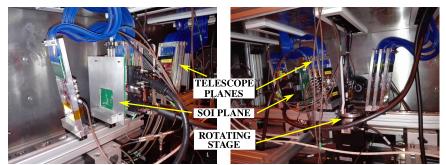


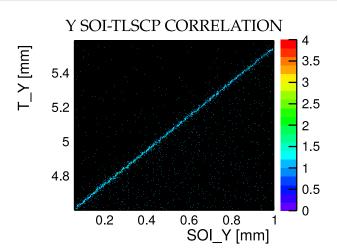
Testbeam setup

DAQ setup:

- main readout PCB + mezzanine boards with different SOI chips
- FPGA PC → Ethernet
- DAQ Software ROOT 6
- possibility of automatic parameters scans
- TESTBEAM: in the CLICdp Timepix3 telescope in the SPS-H6 beamline

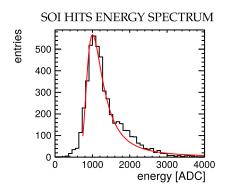


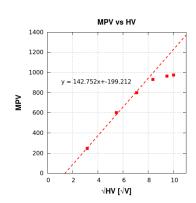




- good correlation with telescope
- large background due to long integration time of SOI pixel

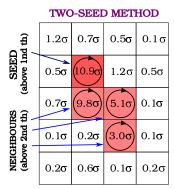
- Landau energy spectra of SOI hits after clusterization. Plot shows all hits (before track association).
- The low energy tail most probably comes from readout issues.
- MPV signal saturates above 80V (default biasing was 90V).





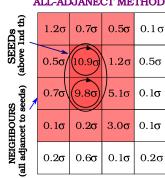
Clusterization methods

Different methods of clusterization in order to improve position calculation:



- Find pixels with signal above first threshold (signal > $9\sigma = 9 \times \text{pixel noise}$)
- Find all adjacent pixels above second threshold (signal $> 2\sigma$)
- When any pixel found, repeat algorithm for each new one.
- 4-pixel cluster is found.

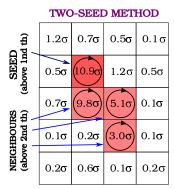
ALL-ADJANECT METHOD



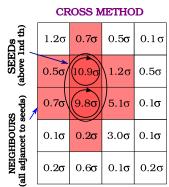
- Find pixel with signal above threshold (signal $> 9\sigma$)
- When seed found, found all next adjacent seeds and repeat for each new one.
- Add to cluster all seeds neighbours
- 12-pixel cluster found.

Clusterization methods

Different methods of clusterization in order to improve position calculation:



- Find pixels with signal above first threshold (signal > $9\sigma = 9 \times \text{pixel noise}$)
- Find all adjacent pixels above second threshold (signal $> 2\sigma$)
- When any pixel found, repeat algorithm for each new one.
- 4-pixel cluster is found.

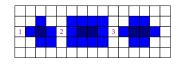


- Find pixel with signal above threshold (signal $> 9\sigma$)
- When seed found, found all next adjacent seeds and repeat for each new one.
- Add to cluster all seeds neighbours in "cross" pattern
- 8-pixel cluster found.

Two-seed method

mean cluster size: 3.7 pixels

asymmetry in resolution in x and in y direction



All-adjacent method

- mainly 2-seed clusters (50%), 1-seed cluster (36%)
- about 80% less reconstructed clusters then in two-seed methods
- resolution in x and in y consistent
- threshold condition used: $30 \times pixel$ noise (around 500 ADC) \rightarrow high, but it is still 30% of most energetic pixel in cluster

Cross method

- similar to all-adjacent, but does not take neighbours on diagonal to seed.
- · gives the same results as all-adjacent method

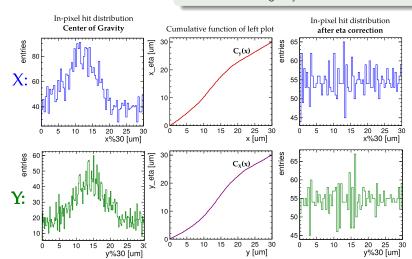
Conclusion

Two-seed method gives the best results in case of energy resolution, but the worse for spatial resolution. All-adjacent and cross methods are the best for position reconstruction, but give pure energy resolution.

For position reconstruction two methods were tested:

- Center of Gravity
- Eta correction

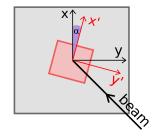
The in-pixel distribution is plotted \rightarrow the cumulative function of this distribution is calculated: $C_X(x) \rightarrow$ the corrected position x_{ETA} is given by: $x_{ETA} = C_X(x_{COG})$, where x_{COG} is the hit position obtained from center of gravity method.



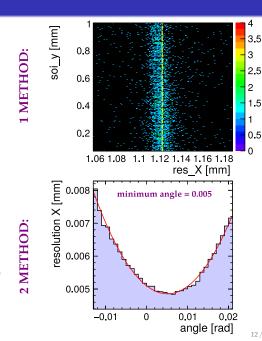
Alignment of SOI pixel chip

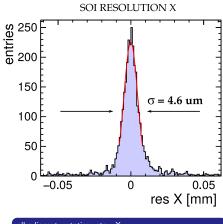
Two alignment methods were applied:

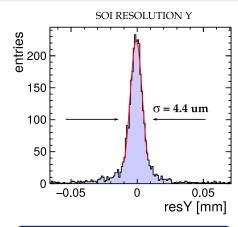
- 1 slope of soi y hit position versus residuum x.
- minimum residuum versus rotation angle.



- both methods gave the same angle
- rotation angle is: $\alpha_{rot} = 0.005 [rad] = 0.285 [deg]$







all-adjacent, rotation, eta - X

 $X_{res} = 4.6 \ \mu m$

all-adjacent, rotation, eta - Y

 $Y_{res} = 4.4 \ \mu m$

Taking into account the telescope resolution ($\sigma_T = \sim 2\mu m$) the SOI resolution is around $\sigma_{SOI} = \sim 4 \mu m$.

- The SOI pixel detector was tested successfully for the first time in CLICdp testheam.
- Oata analysis including clustering, eta correction and alignment was performed in order to calculate the spatial resolution.
- **Spatial resolution for** 30 μm **SOI** pixels of around 4 μm was obtained.
- Ongoing studies: resolution vs bias voltage, analysis for different wafers.

Close future plans:

- New SOI prototype with larger and more uniform matrix has been fabricated and will be tested in the next testbeam.
- Next chip with timing information is being developed.

THANK YOU FOR ATTENTION!